

Appendix A

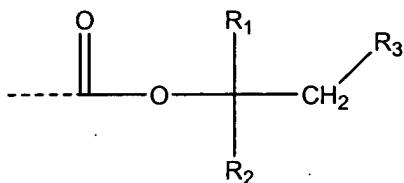
(i) Amendments
in marked-up form to
Claims 1 and 8,

(ii) New Claims 15~24, and

(iii) Status of all other claims

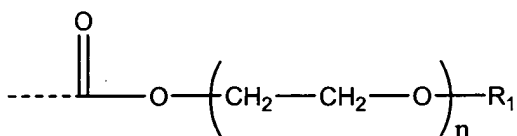
1. (currently amended) A process for fabricating an electronic device comprising:

(a) coating a substrate with a positive photo-imageable protective layer comprising a polymer ~~comprising~~ consisting essentially of, as polymerized units, monomers of which (i) at least 65 mole percent ~~comprise a structure selected from the group consisting of~~ have a first structure as follows:



where R₁ is hydrogen or lower alkyl; R₂ is a lower alkyl; and R₃ is hydrogen or a lower alkyl where the definition of lower alkyl includes alkyl groups having 1 to 6 linear or cyclic carbon atoms; and

(ii) from about 10 to about 35 mole percent have a second structure as follows:



where R₁ is hydrogen or lower alkyl and n is an integer of 2 to 3;

- (b) irradiating a first region of said substrate coated with said polymer with UV radiation;
- (c) heating said polymer and said protective layer to convert said polymer;
- (d) developing said converted polymer; and
- (e) irradiating a second region of said substrate coated with said converted polymer.

2~3. (cancelled).

4. (previously presented) The process of Claim 1 further comprising adding to the photo-imageable polymer 0.5-30 mole% of photoacid generator and 10-1000 ppm of photosensitizer.

5. (cancelled).

6. (previously presented) The process of claim 1 wherein said monomers having said first structure are selected from: t-butyl methacrylate, t-butyl acrylate, neopentyl methacrylate, neopentyl acrylate, 1-Bicyclo{2,2,1}heptyl methacrylate, 1-Bicyclo{2,2,1}heptyl

acrylate), 1-Bicyclo{2,1,1}hexyl methacrylate, 1-Bicyclo{2,1,1}hexyl acrylate, 1-Bicyclo{1,1,1}pentyl methacrylate, 1-Bicyclo{1,1,1}pentyl acrylate, 1-adamantyl methacrylate, 1-adamantyl acrylate, and derivatives thereof.

7. (previously presented) The process of claim 1 wherein said monomers having said second structure are selected from 2-ethoxy methacrylate and 2-ethoxy acrylate.

8. (currently amended) The process of claim 1 wherein said polymer further ~~comprises~~ consists essentially of, as polymerized units, up to about 10 mole percent of a monomer selected from methyl methacrylate, methyl acrylate, methacrylic acid, and hydroxyl ethyl methacrylate.

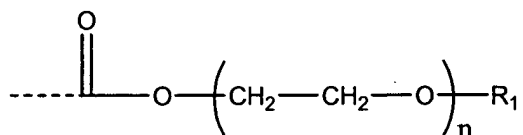
9. (previously presented) The process of claim 1 wherein said polymer comprises about 70 mole percent polymerized units having said first structure and about 30 mole percent polymerized units having said second structure.

10~14. (cancelled).

15. (new) A process for fabricating an electronic device comprising:

(a) coating a substrate with a positive photo-imageable protective layer comprising a polymer consisting essentially of, as polymerized units, monomers (i) of which at least 65 mole percent are selected from the group consisting of 1-Bicyclo{2,2,1}heptyl

methacrylate, 1-Bicyclo{2,2,1}heptyl acrylate), 1-Bicyclo{2,1,1}hexyl methacrylate, 1-Bicyclo{2,1,1}hexyl acrylate, 1-Bicyclo{1,1,1}pentyl methacrylate, 1-Bicyclo{1,1,1}pentyl acrylate, 1-adamantyl methacrylate, 1-adamantyl acrylate, and derivatives thereof; and
(ii) from about 10 to about 35 mole percent have a structure as follows:



where R₁ is hydrogen or lower alkyl and n is an integer of 2 to 3;

- (b) irradiating a first region of said substrate coated with said polymer with UV radiation;
- (c) heating said polymer and said protective layer to convert said polymer;
- (d) developing said converted polymer; and
- (e) irradiating a second region of said substrate coated with said converted polymer.

16. (new) The process of Claim 15 further comprising adding to the photo-imageable polymer 0.5-30 mole% of photoacid generator and 10-1000 ppm of photosensitizer.

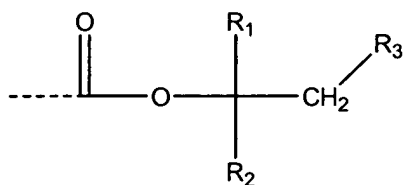
17. (new) The process of claim 15 wherein said monomers having the structure are selected from 2-ethoxy methacrylate and 2-ethoxy acrylate.

18. (new) The process of claim 15 wherein said polymer further consists essentially of, as polymerized units, up to about 10 mole percent of a monomer selected from methyl methacrylate, methyl acrylate, methacrylic acid, and hydroxyl ethyl methacrylate.

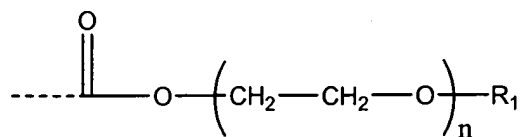
19. (new) The process of claim 15 wherein said polymer comprises about 70 mole percent polymerized units selected from the group (i), and about 30 mole percent polymerized units having the structure (ii).

20. (new) A process for fabricating an electronic device comprising:

(a) coating a substrate with a positive photo-imageable protective layer comprising a polymer comprising, as polymerized units, monomers of which (i) at least 65 mole percent have a first structure as follows:



where R_1 is hydrogen or lower alkyl; R_2 is a lower alkyl; and R_3 is hydrogen or a lower alkyl where the definition of lower alkyl includes alkyl groups having 1 to 6 linear or cyclic carbon atoms; and
(ii) from about 10 to about 35 mole percent have a second structure as follows:



where R_1 is lower alkyl and n is an integer of 2 to 3;

(b) irradiating a first region of said substrate coated with said polymer with UV radiation;

(c) heating said polymer and said protective layer to convert said polymer;

(d) developing said converted polymer; and

(e) irradiating a second region of said substrate coated with said converted polymer.

21. (new) The process of Claim 20 further comprising adding to the photo-imageable polymer 0.5-30 mole% of photoacid generator and 10-1000 ppm of photosensitizer.

22. (new) The process of claim 20 wherein said monomers having said first structure are selected from: t-butyl methacrylate, t-butyl acrylate, neopentyl methacrylate, neopentyl acrylate, 1-Bicyclo{2,2,1}heptyl methacrylate, 1-Bicyclo{2,2,1}heptyl acrylate, 1-Bicyclo{2,1,1}hexyl methacrylate, 1-Bicyclo{2,1,1}hexyl acrylate, 1-Bicyclo{1,1,1}pentyl methacrylate, 1-Bicyclo{1,1,1}pentyl acrylate, 1-adamantyl methacrylate, 1-adamantyl acrylate, and derivatives thereof.

23. (new) The process of claim 20 wherein said polymer further comprises, as polymerized units, up to about 10 mole percent of a monomer selected from methyl methacrylate, methyl acrylate, methacrylic acid, and hydroxyl ethyl methacrylate.

24. (new) The process of claim 20 wherein said polymer comprises about 70 mole percent polymerized units having said first structure and about 30 mole percent polymerized units having said second structure.